

COMPOSITIONS FOR CHEMICAL MECHANICAL POLISHING SILICA AND SILICON NITRIDE HAVING IMPROVED ENDPOINT DETECTION

ABSTRACT

The present invention provides a method of manufacturing a composition for polishing silica and silicon nitride on a semiconductor substrate. The method comprises ion-exchanging carboxylic acid polymer to reduce ammonia and combining by weight percent 0.01 to 5 of the ion-exchanged carboxylic acid polymer with 0.001 to 1 quaternary ammonium compound, 0.001 to 1 phthalic acid and salts thereof, 0.01 to 5 abrasive, and balance water.

No Suitable Figure